


 logo

**Thursday, October 11, 2007**

**Session A - Plenary**  
**Chairman: Serge Tedesco**

Time	N° Paper	Title - Authors, Affiliation, Country
08:15 - 08:40	A-1	<a href="#">Nanoimprint metrology and materials research at NIST (Invited)</a> Chris Soles, <i>NIST, USA</i>
08:40 - 09:05	A-2	<a href="#">Microcontact printing and beyond: From self-assembled monolayers to self-assembled nanoparticles (Invited)</a> Tobias Kraus, S.R.Coyer, A.Decker, E.Delamarche, C.Kümin, L.Malaquin, H. Schmid, H.Wolf, <i>IBM-Zurich, Switzerland</i>
09:05 - 09:30	A-3	<a href="#">Dual Damascene using Step and Flash Imprint Lithography (Invited)</a> Grant Willson, B. Chao, F. Palmieri, WL Jen, J.Owens, K.Sotoodeh, R. Carpio, J. Wetzler, <i>Texas University, USA</i>
09:30 - 09:55	A-4	<a href="#">Nanoimprint Based on Highly Ordered Anodic Porous Alumina (Invited)</a> Hideki Masuda, <i>Tokyo University, Japan</i>
09:55 - 10:20	A-5	<a href="#">Nanoimprint Activities in Korea (Invited)</a> Eung Sug Lee, J.Jeong, K.Kim, D.Choi, J.Choi, J.Lee, K.Choi, G.Kim, S.Lee, D.Lee, A.Altun, J.Shim, S.Lee, <i>KIMM, Korea</i> H.Ahn, H.Rhee, <i>ADP Eng., Korea</i> N.Koo, H.Kurz, <i>AMO, Germany</i> S.Jung, S.Kwak, <i>Samsung, Korea</i> S.Ra, K.Lee, <i>LG, Korea</i>

**Session B - Nanoimprint Tools - Templates**  
**Chairman: Douglas Resnick**

Time	N° Paper	Title - Authors, Affiliation, Country
10:50 - 11:10	B1	<a href="#">Thermal Dip Pen Nanolithography of Polymers</a> Paul Sheehan, A.Larzcuente, W.Lee, M.Yang, L.Whitman, <i>Naval Research Lab, USA</i> W.King, <i>Illinois Uni, USA</i>
11:10 - 11:30	B2	<a href="#">Anti-sticking issues in step and Repeat UV nanoimprint lithography process</a> Sophie Garidel, A.Jouve, M.Zelmann, P.Voisin, <i>CEA/Leti, France</i>
11:30 - 11:50	B3	<a href="#">Sub-50nm patterning over 8 inch area using flexible polymer stamp</a> Sung-Hoon Hong, J.Hwang, H.Lee, <i>Korea University, Korea</i>
11:50 - 12:10	B4	<a href="#">Quantitative study on deteriorated anti-stiction layer in NIL</a> Yoshihiko HIRAI, J.Ishihahra, M.Kayama, <i>Osaka University, Japan</i> A.Koszewski, Z.Rymuza, <i>Warsaw Uni, Poland</i>

**Session C -  $\mu$ TAS & Nanoimprint Bio application**  
**Chairman: Stephan Chou**

Time	N° Paper	Title - Authors, Affiliation, Country
13:40 - 14:05	C1	<a href="#">Microfluidic cell handling and separation using acoustic forces (Invited)</a> Thomas Laurel, <i>Lund University, Sweden</i>
14:05 - 14:30	C2	<a href="#">Microfluidic devices for Ultrafast genetic analysis with Sample -In Answer Out Capability : Where to from here (Invited)</a> James Landers, <i>Virginia University, USA</i>
14:30 - 14:55	C3	<a href="#">New roles for lab on chip technology on drug development (Invited)</a> Sabeth Verpoorte, <i>Groningen University, Germany</i>
14:55 - 15:15	C4	<a href="#">Micro-contact printing of living bacteria arrays for systems biology investigations</a> Damien Baigl, L.Xu, L.Robert, Y.Chen, <i>ENS Paris, France</i> F.Taddei, A.Lindner, <i>INSERM Paris, France</i>
15:15 - 15:35	C5	<a href="#">Improvement of localized surface plasmon resonance sensor sensitivity by using nanoimprinting</a> Hideyuki Yamashita, T.Nishikawa, T.Matsushita, Y.Okuno, <i>OMRON, Japan</i>

## Friday, October 12, 2007

### Session D - Nanoimprint Processes

**Chairman: Grant Willson**

Time	N° Paper	Title - Authors, Affiliation, Country
08:00 - 08:20	D1	<a href="#">Development of Rolling Nanoimprint Technology and Related Applications (invited)</a> Shuo-Hung Chang, F.Chang, H.Lin, W.Lai, T.Chang, C.Ting, J.Tsai, T.Wu, <i>ITRI, Taiwan</i>
08:20 - 08:40	D2	<a href="#">Nanoelectrode lithography using a mold with a pattern defined by substances with different conductances</a> Atsushi Yokoo, H.Namatsu, M.Oda, <i>NTT, Japan</i>
08:40 - 09:00	D3	<a href="#">Controlling linewidth roughness in step and flash imprint lithography</a> Douglas Resnick, N.Khusnatdinov, G.Schmid, D.LaBrake, <i>Molecular Imprints, USA</i>
09:00 - 09:20	D4	<a href="#">Electrokinetically driven micro and nano imprint lithography</a> Isabel Rodriguez, K.Ansari, A.Yee, L.Yee, <i>IMRE, Singapore</i>
09:20 - 09:40	D5	<a href="#">Real-time pattern characterization of high throughput imprint</a> Tanguy Leveder, S.Landis, L.Davoust, <i>CEA/Leti, France</i> S.Soulan, <i>CNRS/LTM, France</i>
09:40 - 10:00	D6	<a href="#">Fabrication of 3D-photonic crystals via UV-nanoimprint lithography</a> Thomas Glinsner, P.Lindner, <i>EV Group, Austria</i> M.Muühlberger, I.Bermair, R.Schöftner, <i>Profactor, Austria</i> K.Hingerl, <i>CD Lab, Austria</i>

### Session E - Nanoimprint Materials

**Chairman: Lifeng Chi**

Time	N° Paper	Title - Authors, Affiliation, Country
10:30 -10:50	E1	<a href="#">Nanophotonic structures fabricated by nanoimprint lithography (invited)</a> Vincent Reboud, N.Kehagias, J. Romero Vivas, CM Sotomayor Torres, <i>Tyndall National Institute, Ireland</i>
10:50 - 11:10	E2	<a href="#">Direct sequential nanoimprint of silica sol-gel resist: a simple route to 3D patterning</a> Christophe Peroz, V.Chauveau, E.Barthel, E.Sondergard, <i>St Gobain, France</i>

11:10 - 11:30	E3	<a href="#">Influence of reactive diluents on curing kinetics, mechanical properties and adhesion of PSS-base UV nanoimprint resist</a> Frances Houle, A.Fornof, H.Truong, D.Miller, E.Simonyi, T.Magbitang, R. Sooriyakuraman, R.Allen, <i>IBM, USA</i>
11:30 - 11:30	E4	<a href="#">Thin Film films characterization (viscosity, adhesion) with rheological nano-probe</a> Sergey Zaitsev, A.Svintsov, O.Trofimov, <i>IMT, Russia</i>
11:50 - 12:10	E5	<a href="#">Nanoscale electronics on flexible substrate by direct nanoimprint of metallic particles</a> Inkyu Park, S.Ko, H.Pan, Costas, P.Grigoropoulos, A.Pisano, <i>Berkeley University, USA</i> E.Lee, J.Jeong, <i>KIMM, Korea</i> J.Frechet, <i>Berkeley Uni, USA</i>

**Session F - Nanoimprint Optical Applications**  
**Chairman: Clivia M. Sottomayor Torres**

Time	N° Paper	Title - Authors, Affiliation, Country
13:40 - 14:00	F1	<a href="#">Optical negative index meta-materials at near-IR wavelength fabricated by nanoimprint lithography (invited)</a> Wei Wu, E.Kim, E.Ponizovskaya, Z.Yu, A.Bratkovsky, S.Wang, R.Williams, <i>HP, USA</i> Y.Liu, X.Zhang, <i>Clifornia Uni, USA</i> N.Fang, <i>Illinois Uni, USA</i>
14:00 - 14:20	F2	<a href="#">Organic light-emitting diodes with photonic crystals Imprinted on Spin-On-Glass</a> Kuniaki Ishihara, M.Fujita, T.Asano, S.Noda, <i>Kyoto University, Japan</i>  H.Ohata, A.Hirasawa, S.Miyaguchi, <i>Pioneer Corp., Japan</i>
14:20 - 14:40	F3	<a href="#">A novel fabrication of large area nano-split-ring structures using nanoimprint</a> Wen-di Li, S.Bai, S.Chou, <i>Princeton University, USA</i>
14:40 - 15:00	F4	<a href="#">Wipe-resistance Improvement with a Low Aspect Pattern by Parabolic Shape Anti-reflection Structure Fabricated by Nanoimprint Lithography</a> Ryosuke Fujioka, O.Nishizaki, Y.Ito, Y.Okuno, <i>OMRON, Japan</i>

**Session G - Other Applications**  
**Chairman: Eung Sug Lee**

Time	N° Paper	Title - Authors, Affiliation, Country
15:00 - 15:20	G1	<a href="#">Hybrid circuit of CMOS and crossbar nanowires by Nanoimprint: Semiconductor Inter Connects (SNIC)</a> Will Tong, M.Cumbie, J.Ellenson, T.Yamashita, D.Lazaroff, L.King, G.Snider, R. Williams, <i>HP, USA</i>
15:20 - 15:40	G2	<a href="#">20 nm phase change memory fabricated using nanoimprint lithography</a> Nianhua Li, C.Peng, S.Chou, <i>Princeton University, USA</i>
15:40 - 16:00	G3	<a href="#">Biomolecule patterning by soft UV nanoimprint lithography and a water soluble interlayer</a> J.Shi, X.Ni, Y.Chen, <i>LPN(CNRS)-ENS, France</i>

16:00 - 16:20	G4	<p><a href="#">Photoluminescence enhancement in metallic nanocomposite printable polymer (invited)</a></p> <p>Vincent Reboud, N.Kehagias, J.Vivas, C.Sotomayor Torres, <i>Tyndall National Institute, Ireland</i></p> <p>M.Zelmann, <i>CNRS/LTM, France</i>  M.Striccoli, T.Placido, <i>CNR, Italy</i>  A.Panniello, <i>Bari Uni., Italy</i>  C.Schuster, F.Reuther, G.Gruetzner, <i>Micro Resist, Germany</i></p>
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**Session Posters - Nanoimprint Applications**  
**Chairman: Frances Perez Murano, Helmut Schiff, Massimo Tormen**

N° Paper	Title - Authors, Affiliation, Country
P-A1	<p><a href="#">Fabrication of ordered lattices of nanopillars of magnetic perovskite</a></p> <p>Irène Fernandez-Cuesta, X.Borrise, F.Perez-Murano, <i>CNM Barcelona, Spain</i>  J.Zabaleta, T.Puig, N.Mestres, X.Obradors, <i>ICM Barcelona, Spain</i></p>
P-A2	<p><a href="#">Soft UV nanoimprint lithography and integration of high density nanostructures into microfluidic chips</a></p> <p>Jian Shi, Y.Chen, <i>LPN-ENS, France</i>  C.Peroz, J.Galas, A.Fang, D.Decanini, <i>CNRS/LPN, France</i></p>
P-A3	<p><a href="#">Simplified nanoimprint lithography process toward protein patterning</a></p> <p>Aritz Retolaza, S.Merino, <i>Fundation Tekniker, Spain</i> P.Heredia, C.Morales, <i>Gaiker, Spain</i>  J.Alduncin, D.Mecerreyes, <i>CEDITEC, Spain</i></p>
P-A4	<p><a href="#">Influences of nanostructure on nanoimprint and nanoprint technology</a></p> <p>Nourdin Boufercha, W.Schäfer, J.Sägebarth, H.Sandmaier, <i>Stuttgart University, Germany</i></p>
P-A5	<p><a href="#">Nanoimprint based fabrication of traceable ID grating pitch standards</a></p> <p>Alexei Bogdanov, D.Goodchild, S.Wingar, <i>IMS, Canada</i>  J.Pekelsky, B.Eves, J.Decker, <i>INMS, Canada</i></p>
P-A6	<p><a href="#">Sub-micrometer channel length OTFTd with ultra-thin organic gate dielectrics by nanoimprint lithography</a></p> <p>Ursula Haas, C.Auner, H.Gold, B.Stadlober, G.Jakopic, <i>Joanneum Research GmbH, Austria</i></p>
P-A7	<p><a href="#">Plastic lasers by nanoimprint lithography</a></p> <p>Dario Pisignano, E.Mele, A.Camposo, P.Del Carro, F.Di Benedetto, L.Persano, R.Cingolani, <i>ISUFI, Italy</i></p>
P-A8	<p><a href="#">Nanoelectromechanical mass sensor fabricated by nanoimprint lithography</a></p> <p>Gang Luo, S.Ghatnekar-Nilsson, D.Hessman, I.Maximov, M.Graczyk, H.Xu, L.Montelius, <i>Lund University, Sweden</i>  A.Kewell, <i>Biosensia Ltd, Ireland</i></p>
P-A9	<p><a href="#">Fabrication of nanostar array by nanoimprint lithography and its application in SERS</a></p> <p>Theodor Veres, B.Cui, K.Li, L.Clime, <i>NMR, Canada</i></p>
P-A10	<p><a href="#">Cost analysis of NIL technology implementation variations</a></p> <p>Lloyd Litt, P.Seidel, <i>SEMATECH, USA</i>  J.Ellenson, <i>HP, USA</i></p>
P-A11	<p><a href="#">Fabrication of ultrasmooth optical substrates by UV nanoimprint</a></p> <p>W. Ito, Y.Kurashima, I.Miyamoto, <i>Tokyo University, Japan</i>  H.Ishii, T.Itatani, H.Hiroshima, <i>AIST, Japan</i></p>
P-A12	<p><a href="#">Injection molding 50nm pillar array for patterned media using a metallic stamp electroformed from nanoimprinted polymeric master</a></p> <p>J.Han, N.Lee, Y.Han, J.Hong, S.Kang, <i>Yonsei University, Korea</i></p>
P-A13	<p><a href="#">Topographical cues in cell biology: micro versus macro</a></p> <p>K.Seunarine, D.Merdith, N.Gadegaard, C.Wilkinson, <i>Glasgow University, UK</i></p>

**Session Posters - Nanoimprint Materials**  
**Chairman: Frances Perez Murano, Helmut Schiff, Massimo Tormen**

<b>N° Paper</b>	<b>Title - Authors, Affiliation, Country</b>
P-M1	<a href="#">Fluorinated materials for nanoimprint process</a> Kentaro Tsunozaki, Y.Kawaguchi, T.Yoneda, <i>Asahi glass, Japan</i>
P-M2	<a href="#">Comparison of the behavior of nanoimprint resists during etching processes</a> Cécile Gourgon, C.Perret, N.Chaix, <i>CNRS LTM, France</i> S.Landis, S.Garcia, <i>CEA/Leti, France</i> F.Reuther, <i>Micro Resist, Germany</i>
P-M3	<a href="#">Low viscosity UV-NIL material development</a> Amendine Jouve, A.Francone, M.Zelsmann, C.Gourgon, J.Boussey, <i>CNRS LTM, France</i>
P-M4	<a href="#">New curing polymer for thermal nanoimprint lithography and mold duplication</a> Nicolas Chaix, C.Gourgon, C.Perret, J.Tortai, F.Mounier, S.Garcia, <i>CNRS LTM, France</i> S.Landis, S.Garcia, <i>CEA/Leti, France</i> F.Reuther, <i>Micro Resist, Germany</i>
P-M5	<a href="#">The annealing effect on an antisticking layer of nanoimprint mold</a> Noriko Yamada, K.Nakamatsu, K.Kanda, Y.Haruyama, S.Matsui, <i>Hyogo University, Japan</i>
P-M6	<a href="#">Highly controlled fabrication of nano-dimensioned 3D cobaltbisdicarbollide-doped microring arrays by electropolymerisation prepared using submerged microcontact printing</a> D. Caballero, M.Pla-Roca, F.Bessueille, C.Mills, F.Teixidor, J.Samitier, A.Errachid, <i>IBEC, Spain</i> E.Crespo, <i>Barcelona Univ. Spain</i>
P-M7	<a href="#">Control of the orientation of polymer crystals by nanoimprint lithography</a> Zhinjin Hu, A.Jonas, <i>Université catholique de Louvain, Belgium</i>
P-M8	<a href="#">Bifunctional chemically patterned flat stamps for microcontact</a> Xuexin Duan, V.Sadhu, A;Perl, M.Peter, D.Reinhoudt, <i>Twente Univ., The Netherlands</i>
P-M9	<a href="#">Hexagonally ordered arrays of SiO<sub>2</sub> nanorods with mesochannels aligned along the longitudinal axes templated from diblock copolymer thin films</a> Aihua Chen, T.Iyoda, <i>Tokyo Institute, Japan</i>
P-M10	<a href="#">Microcontact printing by porous stamps</a> Huaping Xu, J.Huskens, R.Lammertink, D.Reinhoudt, <i>Twente Univ., The Netherlands</i>
P-M11	<a href="#">Comparability of polymers for thermal nanoimprint</a> HC Scheer, N.Bogdanski, M.Wissen, S.Möllenbeck, <i>Wuppertal University, Germany</i>
P-M12	<a href="#">Low k epoxy silsesquioxane resist for UV nanoimprint lithography</a> Mustapha Chouiki, H.Ridaoui, M.Zelsmann, J.Boussey, <i>CNRS LTM, France</i> J. De Girolamo, <i>JF Grenoble Univ, France</i>
P-M13	<a href="#">Microcontact printing patterns of a new calyx[4]arene crown-5 derivative on gold surfaces and their ion recognition properties</a> I.A. Marques de Oliveira, C.Mills, J.Samitier, A.Errachid, <i>IBEC, Spain</i> F.Vocanson, J.Uttaro, <i>Lyon Univ., France</i> Z.Asfari, <i>CNRS/ULP, France</i>

**Session Posters - Nanoimprint Processes**  
**Chairman: Frances Perez Murano, Helmut Schiff, Massimo Tormen**

<b>N° Paper</b>	<b>Title - Authors, Affiliation, Country</b>
P-P1	<a href="#">Electrostatic imprint process for glass</a> Hideki Takagi, S.Miyazamwa, M.Takahashi, R.Maeda, <i>AIST, Japan</i>

P-P2	<a href="#"><u>Advanced mold fabrication for high resolution soft UV nanoimprint lithography</u></a> Nam Il Koo, U.Plachetka, T.Wahlbringk, J.Bolten, C.Moormann, H.Kurz, <i>AMO, Germany</i>
P-P3	<a href="#"><u>A residual-insensitive process for imprint mask pattern fabrication to control the pattern CD and height uniformity</u></a> Atsunori Terasaki, J.Seki, H.Ono, <i>Canon, Japan</i>
P-P4	<a href="#"><u>Nanoscale metal pattern transfer printing</u></a> Kyeongmi Lee, K.Kim, J.Park, S.Kim, S.Song, E.Kim, G.Jung, <i>GIST, Korea</i>
P-P5	<a href="#"><u>Comparison of caged-HSQ and ladder-HSQ patterns produced by room-temperature nanoimprinting</u></a> Ken-itshiro Nakamatsu, Y.Takeuchi, S.Matsui, <i>Hyogo University, Japan</i> N.Taneichi, <i>Tokyo Ohka Kogyo, Japan</i>
P-P6	<a href="#"><u>Effect of UV irradiation on organic-SOG patterns replicated by room-temperature nanoimprinting</u></a>  Ken-itshiro Nakamatsu, Y.Takeuchi, S.Matsui, <i>Hyogo University, Japan</i> N.Taneichi, <i>Tokyo Ohka Kogyo, Japan</i>
P-P7	<a href="#"><u>Nanogap contacts by soft UV nanoimprint lithography</u></a> Anne-Marie Haghiri Gosnet, D.Blondet, F.Hamouda, F.Gaucher, <i>IEF, France</i>
P-P8	<a href="#"><u>Integration Issues in Step and Repeat UV Nanoimprint lithography</u></a> Christelle Charpin-Nicolle, J.Chiaroni, <i>CEA Leti, France</i> J.Massin, <i>STM, France</i> M.Irmscher, <i>IMS Chips, Germany</i> B.Vratzov, <i>NTD Aachen, Germany</i> H. Van Vossen, <i>Twente Univ. The Netherlands</i> P.Gubbini, <i>Molecular Imprints, France</i>
P-P9	<a href="#"><u>Advances in CLIPP for the fabrication of surface modified micro-fluidic devices in non-fluorescing UV cured materials</u></a> Michael Watts, <i>Impattern Solutions, USA</i> R.Sebra, H.Simms, K.Masters, T.Haraldsson, K.Anseth, C.Bowman, <i>Colorado Univ, USA</i>
P-P10	<a href="#"><u>Stamp deformation in nanoimprint : experiments and coarse-grain simulation</u></a> Nikolaos Kehagias, V.Reboud, C.Sotomayor Torres, <i>Tyndall National Inst. Ireland</i> S.Zaitsev, V. Sirotkin, A.Svintsov, <i>IMT, Russia</i>
P-P11	<a href="#"><u>Nanoimprint lithography : no longer a 1x pattern replication process</u></a> Hong Yee Low, K.Chong, <i>IMRE, Singapore</i>
P-P12	<a href="#"><u>&gt;Room temperature nanoimprint lithography on active organic materials</u></a> Elisa Mele, F. Di Benedetto, L.Persano, R.Cingolani, D. Pisignano, <i>ISUFI, Italy</i>
P-P13	<a href="#"><u>Silver nanoparticle patterning based on NIL and electrical deposition</u></a> Nan Lu, B.Yang, H.Xu, L.Chi, <i>Jilin University, P.R. China,</i>
P-P14	<a href="#"><u>Injection molding 50nm scale pattern array</u></a>  Doo Sun Choi, Y.Yoo, T. Je, <i>KIMM, Korea</i>
P-P15	<a href="#"><u>Direct conductive patterns fabricated with nanosilver colloid-mixed UV-curable resin</u></a> Soon Won Lee, K.Dim, D.Choi, J.Jeong, E.Lee, H.Choi, <i>KIMM, Korea</i>
P-P16	<a href="#"><u>Fabrication of 70nm-sized metal line on flexible PET film using nanoimprint lithography</u></a> H.Lee, K.Yang, S.Hong, J.Lee, <i>Korea University, Korea</i>
P-P17	<a href="#"><u>Fabrication of polycarbonate and Si replicas with 50nm patterns using UV and thermal nanoimprint lithography tools</u></a> Jaejong Lee, S.Lee, S.Kim. S.Park, <i>Korea Institute, Korea</i>



P-P18	<a href="#">Fabrication of polycarbonate replicas with 100nm hemisphere patterns using Au self-assembling and thermal nanoimprint lithography tools</a> Seung Woo Lee, S.Park, J.Lee, <i>Korea Institute, Korea</i>
P-P19	<a href="#">Nanoscale patterning using PDMS and polycarbonate replicas by the roll types UV-nanoimprint lithography tools</a> Soo Yeon Park, S.Lee, J.An, J.Lee, <i>Korea Institute, Korea</i>
P-P20	<a href="#">Step and flash processes and technology of photonic crystal patterning : template replication through wafer patterning</a> Mike Miller, C.Brooks, D.Lentz, D.Resnick, D.LaBrake, <i>Molecular Imprints, USA</i>
P-P21	<a href="#">Micro to nano imprinting with flexible film stamps for optical component fabrication</a> Junya Kobayashi, Y.Hatakeyama, N.Kawakami, S.Yagi, <i>NNT Photonics, Japan</i>
P-P22	<a href="#">Advanced hybrid nanoimprint for micro-nano mixed structure</a> Oshihiko Hirai, D.Morihara, H.Kawata, Y.Hirai, <i>Osaka University, Japan</i>
P-P23	<a href="#">Molecular dynamics simulation on glass deformation in nanoimprint lithography</a> Kazuhiro Tada, K.Y.Kimoto, M.Yasuda, S.Horimoto, H.Kawata, Y.Hirai, <i>Osaka University, Japan</i>
P-P24	<a href="#">Study on required polymer characteristics in rapid thermal NIL</a> Oshihiko Hirai, T. Tanabe, M.Shibata, H.Kawata, <i>Osaka University, Japan</i>
P-P25	<a href="#">Time evolution of resist deformation in thermal nanoimprint lithography</a> T.Tanabe, M.Shibata, O.Hirai, <i>Osaka University, Japan</i> Y.Onishi, T.Iwasaki, Y.Iriye, <i>Mizuho Inst., Japan</i>
P-P26	<a href="#">Compliant layer influence on UV-nanoimprinting in a solid parallel-plate setup</a> Michael Muhlberger, I.Bergmair, M.Gusenbauer, R.Schöftner, <i>Profactor, Austria</i> K.Hingerl, <i>Linz CD Lab, Austria</i>
P-P27	<a href="#">Fabrication of nano-Au islands using 2.5D PDMS stamps</a> Wolfgang Schwinger, E. Lausecker, I.Bergmair, R.Schöftner, <i>Profactor, Austria</i> M.Grydlik, T.Fromherz, C.Hasenfuss, <i>Linz Univ, Austria</i>
P-P28	<a href="#">Influence of stamp design on the demolding of microstructures</a> Helmut Schiff, K.Vogelsang, <i>PS Institute, Switzerland</i> S.Bellini, <i>ETH Zurich, Switzerland</i> B.Schmid, <i>Windish Univ, Switzerland</i>
P-P29	<a href="#">Online measurement of demolding forces : from peeling to parallel detachment</a> Vera Trobadelo, H.Schiff, K.Vogelsang, <i>PS Institute, Switzerland</i> S.Merinos, <i>Fundacion Tekniker Guipuzkoa, Spain</i>
P-P30	<a href="#">Evaluation of pressure uniformity by using a pressure-sensitive film on curved nanoimprint lithography</a> Jer Haur Chang, Y.Lee, E.Chen, L.Wang, <i>Taiwan University, Taiwan</i>
P-P31	<a href="#">Speeding-up the imprinting cycle in NIL by stamps with integrated heater</a> Massimo Tormen, R.Malureanu, <i>TASC, Italy</i> O.Hansen, A.Kristensen, <i>Technical Univ of Denmark, Denmark</i>
P-P32	<a href="#">Gel permeation printing of oleophilic gold nanoparticles</a> Masaru Nagakawa, M.Tagaya, T.Iyoda, <i>Tokyo Institute, Japan</i>
P-P33	<a href="#">Nano processing of a gold thin film by thermal nanoimprint lithography and wet etching using a photo-crosslinkable monolayer</a> Hirokazu Oda, M.Nakagawa, <i>Tokyo Institute, Japan</i> T.Ohtake, T.Takaoka, <i>Tsukuba Corp Research, Japan</i>
P-P34	<a href="#">Multiple lengthscale patterning of ferrocenylsilane (block co) polymers by top down methods</a>  Canet Acikgoz, M.Hempenius, G.Vancso, J.Huskens, <i>Twente University, The Netherlands</i>

P-P35	<a href="#">Reverse nanoimprint lithography using hydrogen silesquioxane (HSQ) films</a> Nicolaos Kehagias, V.Reboud, C.Sotomayor Torres, <i>Tyndall National Institute, Ireland</i>
P-P36	<a href="#">Continuous roll to roll method to produce fluidics channels</a> Tapio Makela, T.Haatainen, P.Majander, J.Ahopelto, <i>VTT Micro Nano, Finland</i>
P-P37	<a href="#">Defect issues during lateral filling of trenches</a> Saskia Mollenbeck, N.Bogdanski, M.Wissen, H.Scheer, J.Zajadacz, K.Zimmer, <i>Wuppertal University, Gemany</i>
P-P38	<a href="#">Thermal imprint of polymers below the critical molecular weight</a> Nicolas Bogdanski, M.Wissen, S.Mollenbeck, H.Scheer, <i>Wuppertal University, Germany</i>
P-P39	<a href="#">Fabrication of metallic by nanoimprint of metallic glasses for patterned media</a> Y Saotome, K.Amiya, A.Urata, A.Makino, N.Nishiyama, W.Yamagishi, E.Makate, H. Kimura, A.Inoue, <i>Tohoku University, Japan</i>
P-P40	<a href="#">Imprint of Deep, High Aspect-Ratio Microstructures in Functional Materials</a> Xiaogan Liang, S.Wang, K.Morton, Z.Fu, S.Chou, <i>Princeton University, USA</i>
P-P41	<a href="#">A finite element mesh tailored to full NIL process modelling: hot embossing, cool-down and stamp release</a> D.A Mendels, <i>National Physical Lab Teddington, UK</i> I.Fernandez-Cuesta, X.Borrise, F.Perez-Murano, <i>CNM Barcelona, Spain</i> A.Retolaza, S.Merino, <i>Fundacion Tekniker, Guipuzkoa, Spain</i> O.Hansen, A.Kristensen, <i>Nano DTU, Denmak</i>
P-P42	<a href="#">Residue Controlling Imprint Process for Printed Circuit Board</a> Seunghyun Ra, S. Lee, J. Kwak, J. Moon, <i>Samsung, Korea</i>

### Session Posters - Nanoimprint Templates

**Chairman: Frances Perez Murano, Helmut Schiff, Massimo Tormen**

N° Paper	Title - Authors, Affiliation, Country
P-T1	<a href="#">80nm thermal nanoimprint using electroformed-Ni mold</a> M. Takahashi, Harataka Mekaru, A.Ueno, <i>AIST, Japan</i> H.Hamada, D.Deguchi, <i>NTT, Japan</i>
P-T2	<a href="#">Explorer of a mold and its release coating with long-term UV-nanoimprints</a> Hiroshi Hiroshima, M.Ogiwara, A.Ueno, <i>AIST, Japan</i>
P-T3	<a href="#">Process development for UV step and repeat nanoimprint lithography using an HSQ-based nanopatterned mold</a> Sophie Garidel, C.Constancias, C.Licitra, F.Muller, <i>CEA/Leti, France</i>
P-T4	<a href="#">Mold replication technology for nanoimprint</a> Masahiko Ogino, K.Ohashi, N.Sato, K.Murao, T.Haba, H.Nakano, H.Suzuki, A. Miyauchi, <i>Hitachi, Japan</i> K.Sakaue, S.Nagai, <i>Hitachi Industrial, Japan</i>
P-T5	<a href="#">Template release for vinyl ether UV-cure nanoimprint resist</a> Frances Houle, D.Miller, M.Hart, H.Ito, R.Allen, <i>IBM, USA</i>
P-T6	<a href="#">From NIL to functional surface patterning</a> Lifeng Chi, W.Hu, N.lu, <i>Jilin university, PR China</i> H.Fuchs, <i>Munster Univ., Germany</i> N.Kehagias, V. Reboud, C. Sotomayor Torres, <i>Tyndall Institute, Ireland</i>
P-T7	<a href="#">A simplified process for high-resolution UV-NIL templates fabrication</a> Laurent Jalabert, E.Daran, J.Doucet, F. Carcenac, P.Dubreuil, O.Bouchard, S. Henandez, <i>LAAS, France</i> P.Sales, G.Benassayag, <i>CEMES, France</i> J.Navarro, <i>LAPLACE, France</i>
P-T8	<a href="#">Two steps for silicon molds fabrication using maN2403 negative tone resist</a> Franck Carcenac, E.Daran, P.Dubreuil, L.Jalabert, C.Severac, C.Vieu, <i>LAAS, France</i>



P-T9	<a href="#">Replication of stamps for UV-NIL using Ormocers</a> Iris Bergmair, M. Mühlberger, R.Schöftner, <i>Profactor, Austria</i> M.Vogler, <i>Micro Resist, Germany</i> K.Hingerl, <i>Linz CD Lab, Austria</i> H.Schmidt, E.Kley, <i>Jena Univ., Germany</i>
P-T10	<a href="#">Surface modification of nickel stamps for mold release</a> Ilsang Maeng, S.Ra, J.Kwak, <i>Samsung, Korea</i>
P-T11	<a href="#">Two level stamps fabrication using MESD method</a> Seunghyun Ra, <i>Samsung, Korea</i> J. Yoon, <i>KAIST, Korea</i>
P-T12	<a href="#">High resolution mold fabrication for nanoimprint lithography system in a fast cycle at low cost</a> Marylène Palard, S.Banerjee, <i>Texas University, USA</i>
P-T13	<a href="#">Characterisation of nanoimprinted structures by sub-wavelength diffraction gratings and photoacoustic metrology</a> Timothy Kehoe, V.Reboud, N.Kehagias, C.Sotomayor Torres, <i>Tyndall National Institute, Ireland</i> S.Landis, C.Gorgon, <i>CNRS/LTM, France</i> J.Bryner, J.Vollmann, J.Dual, <i>ETH Zurich, Switzerland</i>
P-T14	<a href="#">Fabrication of a wafer size UV-NIL stamp by step and stamp imprint lithography</a> Tomi Haatainen, M.Majander, T.Maukela, J.Ahopelto, <i>VTT Micro Nano, Finland</i> Y.Kawaguchi, <i>Asahi Gall, Japan</i>
P-T15	<a href="#">Replication of Transparent Nanostamp by Using Organic/Inorganic Hybrid Materials for UV Nanoimprint Process</a> Namseok Lee, S. Kang, <i>Yonsee University, Korea</i> G. Domann, M. Popall, <i>FhG ISC, Germany</i>
P-T16	<a href="#">Mold fabrication technique by using hybrid EB-writing with 100kV-SB and 50kV-VSB writers</a> Morihsa Hoga, H.Fujita, M.Ishikawa, M.Sakaki, N.Kuwahara, T. Takikawa, H.Sano, N. Hayashi, <i>Dai Nippon Printing Co., Japan</i>
P-T17	<a href="#">A Novel Self alignment Fabrication of 20 nm T-gate Nanoimprint Molds</a> Can Peng, S.Chou, <i>Princeton University, USA</i>
P-T18	<a href="#">Development of a high durable mold release agent for Nanoimprint Lithography</a> Katsuya Ueno, Yasuhide Kawaguchi, Nobuyuki Kasahara, Kazuhiko Yamada, <i>Asahi Glass, Japan</i>

### Session Posters - Nanoimprint Templates

**Chairman: Frances Perez Murano, Helmut Schiff, Massimo Tormen**

N° Paper	Title - Authors, Affiliation, Country
P-To1	<a href="#">Topography and layer stack condition measurement on imprinted wafers</a> Koichi Sentoku, E.Kawakami, K.Kasumi, H.Ina, <i>Canon, Japan</i>
P-To2	<a href="#">Optimal resist dispensing in step and flash NIL</a> Sergey Zaitsef, V.Sirotkin, A.Svintsov, <i>IMPT, Russia</i>
P-To3	<a href="#">Dual grating aligning system for UV nanoimprint machine and its signal characteristics</a> Geehong Kim, J.Lee, <i>KIMM, Korea</i>
P-To4	<a href="#">Dual side UV nanoimprint with roll stamp for mass production</a> Sung-un Jung, S.Kwak, J.Jeong, E.Lee, <i>Kornic Systems Co, Korea</i>
P-To5	<a href="#">Simulation of exposure and development process in 3D electron beam lithography</a> Michael Hirtz, H.Fichs, L.Chi, <i>Physikaliches Institute, Germany</i> M.Kahl, <i>Raith, Germany</i>

P-To6	<a href="#">Step and stamp imprint lithography for stitching patterns in large stamp manufacturing</a> Gilbert Lecarpentier, J. Mottet, <i>SET, France</i> T.Haatainen, P.Majander, J.Ahopelto, <i>VTT, Finland</i>
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